IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of:
Kajiwara, et al.

Serial No. to be assigned	Atty. Docket No. A-70092/RMA/WEN
Filed: herewith	
Chemical Mechanical Polishing Apparatus And Method Having A Retaining Ring with A Contoured Surface	June 4, 2001 San Francisco, CA

INFORMATION DISCLOSURE STATEMENT

Assistant Commissioner for Patents
Washington D.C. 20231

Sir:

Applicant hereby submits patents, publications, or other information of which he is aware, which he believes may be material to the examination of the above referenced application and in respect to which there may be a duty to disclose in accordance with 37 C.F.R. §1.56. The disclosure contained herein is not intended to constitute an admission that any patent, publication, or other information referred to is "prior art" for this invention unless specifically designated as such. In accordance with 37 C.F.R. §1.97 (b), the filing of this Information Disclosure Statement shall not be construed to mean that a search has been made or that no other material information as defined by 37 C.F.R. §1.56 exists.
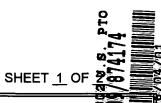
No fee is due.

Respectfully submitted,

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INFORMATION DISCLOSURE

CITATION

PTO-1449

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APPLICANT Kajiwara, et al.	
FILING DATE	GROUP

U.S. PATENT DOCUMENTS

EXAMINER'S INITIALS	PATENT NO.	DATE	NAME	CLASS	SUBCLASS	FILING DATE

FOREIGN PATENT DOCUMENTS

EXAMINER'S INITIALS	PATENT NO.	DATE	COUNTRY	CLASS	SUBCLASS	Translation Yes	No
,	2 315 694 A	Feb 1998	GB				
,	2 307 342 A	May 1997	GB				

OTHER PUBLICATIONS

EXAMINER	DATE CONSIDERED